

Chambers *sub. 1* *sub. 2* *sub. 3*
a third chamber capable of taking said substrate out of said multi-chamber system after
depositing said gate insulating film.

J 2
83.(Amended) A multi-chamber system comprising:

a first chamber for irradiating a lamp light to a semiconductor film formed over a substrate;
a second chamber for performing at least one heating process;
a third chamber for depositing an insulating film; and
a fourth chamber capable of taking said substrate out of said multi-chamber system.

J 3 *sub. 1* *sub. 2*
86.(Amended) A multi-chamber system comprising:

a first chamber for irradiating a laser light to a semiconductor film formed over a substrate
under an atmosphere containing an oxidizing atmosphere;
a second chamber for depositing a gate insulating film on said semiconductor film;
a third chamber capable of taking said substrate out of said multi-chamber system after
depositing said gate insulating film; and
a means for transporting said substrate among said first, second and third chambers.

J 4
89.(Amended) A multi-chamber system comprising:

a first chamber for irradiating a lamp light to a semiconductor film formed over a substrate;
a second chamber for performing at least one heating process;
a third chamber for depositing an insulating film;
a fourth chamber capable of taking said substrate out of said multi-chamber system;
a means for transporting said substrate among said first, second, third and fourth chambers.

J 5 *sub. 1* *sub. 2* *sub. 3*
92.(Amended) A multi-chamber system comprising:

a first chamber for irradiating a laser light to a semiconductor film formed over a substrate
under an oxidizing atmosphere;
a second chamber for depositing a gate insulating film; and
a third chamber for putting said substrate in said multi-chamber system and for taking said
substrate out of said multi-chamber system,

wherein said multi-chamber system is capable of depositing said gate insulating film on said semiconductor film irradiated with said laser light.

95.(Amended) A multi-chamber system comprising:

a first chamber for irradiating a lamp light to a semiconductor film formed over a substrate;
a second chamber for performing at least one heating process;
a third chamber for depositing an insulating film; and
a fourth chamber for putting said substrate in said multi-chamber system and for taking said substrate out of said multi-chamber system.

98.(Amended) A multi-chamber system comprising:

a first chamber for irradiating a laser light to a semiconductor film formed over a substrate under an oxidizing atmosphere;
a second chamber for depositing a gate insulating film;
a third chamber for putting said substrate in said multi-chamber system and for taking said substrate out of said multi-chamber system; and
a means for transporting said substrate among said first, second and third chambers,
wherein said multi-chamber system is capable of depositing said gate insulating film on said semiconductor film irradiated with said laser light.

101.(Amended) A multi-chamber system comprising:

a first chamber for irradiating a lamp light to a semiconductor film formed over a substrate;
a second chamber for performing at least one heating process;
a third chamber for depositing an insulating film;
a fourth chamber for putting said substrate in said multi-chamber system and for taking said substrate out of said multi-chamber system; and
a means for transporting said substrate among said first, second, third and fourth chambers.

104.(Amended) A multi-chamber system according to claim 80 wherein said laser comprises an excimer laser or a YAG laser.

105.(Amended) A multi-chamber system according to claim 80 wherein said laser light has a rectangular shape on an irradiated surface.

106.(Amended) A multi-chamber system according to claim 83 wherein said laser comprises an excimer laser or a YAG laser.

107.(Amended) A multi-chamber system according to claim 83 wherein said laser light has a rectangular shape on an irradiated surface.

108.(Amended) A multi-chamber system according to claim 86 wherein said laser comprises an excimer laser or a YAG laser.

109.(Amended) A multi-chamber system according to claim 86 wherein said laser light has a rectangular shape on an irradiated surface.

111.(Amended) A multi-chamber system according to claim 89 wherein said laser comprises an excimer laser or a YAG laser.

112.(Amended) A multi-chamber system according to claim 89 wherein said laser light has a rectangular shape on an irradiated surface.

114.(Amended) A multi-chamber system according to claim 92 wherein said laser comprises an excimer laser or a YAG laser.

115.(Amended) A multi-chamber system according to claim 92 wherein said laser light has a rectangular shape on an irradiated surface.

116.(Amended) A multi-chamber system according to claim 95 wherein said laser comprises an excimer laser or a YAG laser.

117. (Amended) A multi-chamber system according to claim 95 wherein said laser light has a rectangular shape on an irradiated surface.

118. (Amended) A multi-chamber system according to claim 98 wherein said laser comprises an excimer laser or a YAG laser.

119. (Amended) A multi-chamber system according to claim 98 wherein said laser light has a rectangular shape on an irradiated surface.

121. (Amended) A multi-chamber system according to claim 101 wherein said laser comprises an excimer laser or a YAG laser.

122. (Amended) A multi-chamber system according to claim 101 wherein said laser light has a rectangular shape on an irradiated surface.

Please add new claims 124-131 as follows:

--124. (New) A multi-chamber system according to claim 83 wherein said lamp is one selected from the group consisting of a xenon lamp, a krypton lamp, and a halogen lamp.

125. (New) A multi-chamber system according to claim 83 wherein said insulating film comprises a gate insulating film.

126. (New) A multi-chamber system according to claim 89 wherein said lamp is one selected from the group consisting of a xenon lamp, a krypton lamp, and a halogen lamp.

127. (New) A multi-chamber system according to claim 89 wherein said insulating film comprises a gate insulating film.

128. (New) A multi-chamber system according to claim 95 wherein said lamp is one